

## WHAT IS CLAIMED IS:

1. A temperature adjusting system comprising:
  - a chamber;
  - a cooler which cools an inert gas to be supplied
  - 5 to said chamber;
  - a circulating path which circulates the inert gas through said chamber and said cooler;
  - a first shut-off valve arranged in said circulating path between said chamber and an outlet
  - 10 port of said cooler; and
  - a second shut-off valve arranged in said circulating path between said chamber and an inlet port of said cooler.
2. The system according to claim 1, comprising a
- 15 filter upstream of said first shut-off valve and downstream of said second shut-off valves.
3. The system according to claim 1, further comprising a blower arranged in said circulating path upstream of said second shut-off valve.
- 20 4. The system according to claim 1, further comprising a suction path to be connected to the circulating path downstream of said first shut-off valve through a suction valve in order to introduce a gas in an external atmosphere to said circulating path.
- 25 5. The system according to claim 3, further comprising an exhaust path to be connected to said circulating path upstream of said second shut-off valve

and downstream of said blower through an exhaust valve in order to exhaust a gas in said circulating path to the external atmosphere.

6. The system according to claim 4, further  
5 comprising an exhaust path to be connected to said circulating path upstream of said second shut-off valve and downstream of said blower through an exhaust valve in order to exhaust a gas in said circulating path to the external atmosphere.

10 7. An exposure apparatus for transferring a pattern onto a substrate with exposure light, comprising:

a chamber having therein a space where exposure light passes;

15 a cooler which cools an inert gas to be supplied to said chamber;

a circulating path which circulates the inert gas through said chamber and said cooler;

a first shut-off valve arranged in said circulating path between said chamber and an outlet  
20 port of said cooler; and

a second shut-off valve arranged in said circulating path between said chamber and an inlet port of said cooler.

8. A device manufacturing method of forming a  
25 pattern onto a substrate by using an exposure apparatus according to claim 7.